



HJT 硅片管式吸杂前清洗设备-GW级

HJT Wafer Tube Cleaning Equipment-GW Level

特点描述

- 高效节能的烘干系统;
- 臭氧水洗采用常压大流量混合, 确保臭氧混合有效性;
- 冷/热水慢提拉工艺, 更宽的工艺窗口;
- 高效过滤与初效过滤相结合, 保证设备内更高的洁净度。

Features

- Efficient and energy-saving drying system;
- Atmospheric mixed ozone washing, ensure mixing effectiveness;
- Cold/hot water slow lift process, wider process window;
- Combining efficient filtration with preliminary filtration, ensure higher cleanliness inside the device.

技术性能

设备产能>32000片/小时(每篮232片半片)(1.2GW@210半片、1GW@182半片);
碎片率<0.3‰;
反射率>40%,单片抛光均匀性<1%,片间抛光均匀性<1%;
台阶宽度大于15um ;
设备Uptime:≥97%;
设备臭氧水浓度> 40 ppm ;
设备产品良率>99.9%。

Performance

Equipment capacity >32000Pcs/h(232pcs half cell per basket)
(1.2GW@210B、1GW@182B)
Breakage rate< 0.3‰;
Reflectivity> 40%, texture uniformity<1%,
Texture uniformity between cell<1%;
Step width greater than 15um ;
Uptime: ≥97%;
Ozone concentration > 40 ppm ;
Product yield >99.9%

技术参数 Parameter

项目 Item	数值 Value
清洗流程 Cleaning process	O3-Clean→SDE→O3-Clean→DHF→DRY